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Docket No.: 50090-473

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

:

Shunichi ABE, et al.

:

Serial No.:

:

Group Art Unit:

:

Filed: March 06, 2002

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Examiner:

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For: SEMICONDUCTOR DEVICE, METHOD OF FABRICATING THE SAME AND
SEMICONDUCTOR DEVICE FABRICATING APPARATUS

JC979 U.S. PTO
10/090842
03/06/02



INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, DC 20231

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

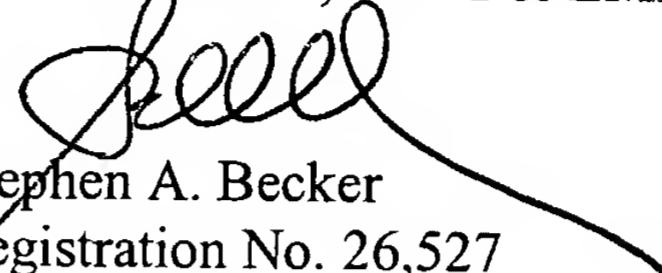
This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits.

Serial No.:

No certification or fee is required.

Respectfully submitted,

MCDERMOTT, WILL & EMERY


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INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
50090-473

SERIAL NO.

JC979 U.S. Pro
10/090842

03/06/02

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	2000-269243	09/29/2000	Japan (w/ English Abstract)				
	10-32307	02/03/1998	Japan (w/ English Abstract)				
	6-151701	05/31/1994	Japan (w/ English Abstract)				
	2000-294724	10/20/2000	Japan (w/ English Abstract)				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.